ABSTRACT

The invention relates to a method of manufacturing a matrix for the production of optical disks by applying a photoresist film to an unstructured matrix plate and structuring the photoresist film by selectively exposing and developing said film. When a negatively acting photoresist is used, the matrix may be metal-plated on the surface provided with the photoresist film after structuring of the photoresist film. Structuring of the photoresist film may comprise heating of the selectively exposed photoresist film, integral exposure of the photoresist film prior to developing and heating of the photoresist film following developing. The unstructured matrix plate may be etched, using the structured photoresist film as a mask, after which the photoresist film is removed to produce the matrix. Prior to applying the photoresist film to the unstructured matrix plate a metal film may be applied, to a thickness equal to the height of the structure desired in the matrix. When a positively acting photoresist is used, a metal film is applied to the unstructured matrix plate, using the structured photoresist film as a mask, after which the photoresist film is removed to produce the matrix. A filling process may be used thereby.

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